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Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Claims 1 - 14. (Cancelled).

- 15. (Currently Amended) A composition comprising [[p]]Partly hydrophobic silica particles said partly hydrophobic silica particles having a contact angle θ in air for water of less than 180°, a degree of coverage τ of the surface of the silica with silylating agent residues, based on the total silica particle surface area, of $1\% < \tau < 50\%$, a density of surface silanol groups SiOH ranging between a minimum of 0.9 and a maximum of 1.7 SiOH/nm² particle surface area, and having a carbon content of more than 0% and up to 2.0% by weight, and a methanol number of less than 30, said partly hydrophobic silica prepared by a process comprising silylating silica particles with
 - I) an organosilane of the formula

$$R^1_n SiX_{4-n}$$

where n is 1, 2 or 3

or mixtures of these organosilanes,

- R¹ being a monovalent, optionally halogenated hydrocarbon radical having 1 to 24 carbon atoms, being identical or different at each occurrence, and being saturated, aromatic, monounsaturated, or polyunsaturated,
- X each independently being halogen, a nitrogen radical, OR^2 , $OCOR^2$, or $O(CH_2)_xOR^2$,
- R² being hydrogen or a monovalent hydrocarbon radical having 1 to 12 carbon atoms, and
- x being 1, 2 or 3;

or

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II) an organosiloxane composed of units of the formula

$$(R_{3}^{1}SiO_{1/2})$$
, and/or
 $(R_{2}^{1}SiO_{2/2})$, and/or
 $(R_{3}^{1}SiO_{3/2})$

where R1 is as defined above, or mixtures thereof,

the number of these units in one organosiloxane being at least 2; and I and II being used alone or in any desired mixtures in a total amount of from 0.015 mmol/g to 0.15 mmol/g per 100 m²/g of silica BET surface area measured by the BET method in accordance with DIN 66131 and 66132.

16. (Currently Amended) The composition particles of claim 15, wherein said silylating is performed with an organosiloxane composed of units of the formula (II)

$$(R_{3}^{1}SiO_{1/2})$$
, and/or
 $(R_{2}^{1}SiO_{2/2})$, and/or
 $(R_{3}^{1}SiO_{3/2})$

where R1 is as defined above, or mixtures thereof,

the number of these units in one organosiloxane being at least 2; II being used in a total amount of from 0.015 mmol/g to 0.15 mmol/g per 100 m²/g of silica BET surface area measured by the BET method in accordance with DIN 66131 and 66132.

17. (Currently Amended) The composition particles of claim [[7]] 15, wherein said silylating is performed with an organosilane of the formula

$$R_3SiX_{y-n}$$

where n is 1, 2, or 3, or a mixture of these organosilanes, where R³ is a monovalent saturated hydrocarbon radical having 1 to 24 carbon atoms or a monovalent or monovalent aromatic hydrocarbon radical having 6 to 24 carbon atoms, each R³ being the same or different,

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- X each independently being halogen, a nitrogen radical, OR^2 , $OCOR^2$, or $O(CH_2)_xOR^2$,
- R² being hydrogen or a monovalent hydrocarbon radical having 1 to 12 carbon atoms, and being 1, 2 or 3.
- 18. (Currently Amended) The composition <u>particles</u> of claim 17, wherein said step of silylating is additionally performed with an organosiloxane of the formula (II).
- 19. (Currently Amended) The composition particles of claim 17, wherein each R³ individually is selected from the group consisting of methyl, ethyl, propyl, butyl, pentyl, hexyl, octyl, decyl, dodecyl, hexadecyl, octadecyl, phenyl, biphenyl, napthyl, benzyl, ethylpenyl, tolyl, and xylyl radicals.

20. - 29. (Cancelled).

- 30. (Currently Amended) The composition <u>particles</u> of claim 15, wherein said partly hydrophobic silica has a methanol number less than 20.
- 31. (Currently Amended) The composition particles of claim 15, wherein said partly hydrophobic silica has a carbon content of 0.1 to 0.5 weight percent per each 100 m²/g of surface area.